## Ismo T S Rauha

List of Publications by Year in descending order

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#	Article	IF	CITATIONS
1	Are Two Azo Groups Better than One? Investigating the Photoresponse of Polymer-Bisazobenzene Complexes. Chemistry of Materials, 2014, 26, 5089-5096.	3.2	57
2	Chemical compatibility of fused filament fabrication-based 3-D printed components with solutions commonly used in semiconductor wet processing. Additive Manufacturing, 2018, 23, 99-107.	1.7	33
3	Photomechanical Energy Transfer to Photopassive Polymers through Hydrogen and Halogen Bonds. Macromolecules, 2015, 48, 7535-7542.	2.2	27
4	Approaches to open source 3-D printable probe positioners and micromanipulators for probe stations. HardwareX, 2018, 4, e00042.	1.1	18
5	Towards national policy for open source hardware research: The case of Finland. Technological Forecasting and Social Change, 2020, 155, 119986.	6.2	17
6	Compatibility of 3-D printed devices in cleanroom environments for semiconductor processing. Materials Science in Semiconductor Processing, 2019, 89, 59-67.	1.9	12
7	Efficient surface passivation of black silicon using spatial atomic layer deposition. Energy Procedia, 2017, 124, 282-287.	1.8	8
8	Impact of black silicon on light―and elevated temperature―nduced degradation in industrial passivated emitter and rear cells. Progress in Photovoltaics: Research and Applications, 2019, 27, 918-925.	4.4	8
9	Atomic layer deposited aluminum oxide mitigates outgassing from fused filament fabrication–based 3-D printed components. Surface and Coatings Technology, 2020, 386, 125459.	2.2	7
10	Observation of Si 2p Core‣evel Shift in Si/Highâ€₽̂ Dielectric Interfaces Containing a Negative Charge. Advanced Electronic Materials, 2021, 7, 2100034.	2.6	7
11	Vacuum outgassing characteristics of unpigmented 3D printed polymers coated with atomic layer deposited alumina. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2020, 38,	0.9	6
12	AlOx surface passivation of black silicon by spatial ALD: Stability under light soaking and damp heat exposure. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2020, 38, 022401.	0.9	6
13	Fast Wafer-Level Characterization of Silicon Photodetectors by Photoluminescence Imaging. IEEE Transactions on Electron Devices, 2022, 69, 2449-2456.	1.6	5
14	Stability of the surface passivation properties of atomic layer deposited aluminum oxide in damp heat conditions. AIP Conference Proceedings, 2019, , .	0.3	3
15	Increased surface recombination in crystalline silicon under light soaking due to Cu contamination. Solar Energy Materials and Solar Cells, 2021, 232, 111360.	3.0	0